

PATENT ABSTRACTS OF JAPAN

(11)Publication number : **2002-328098**

(43)Date of publication of
application : **15.11.2002**

(51)Int.Cl.

G01N 21/892

G01N 1/00

G01N 21/88

(21)Application
number : **2001-132537**

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(22)Date of filing : **27.04.2001**

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(54) SIMULATION DEFECT SAMPLE AND SENSITIVITY DETECTING METHOD FOR DEFECTIVE INSPECTING DEVICE

(57)Abstract:

PROBLEM TO BE SOLVED: To easily and efficiently detect sensitivity of a defective inspecting device.

SOLUTION: A linear simulation defect 13 is formed on a base member 11 of the same configuration as a subject using a laser marking device 12, constituting a simulation defect sample 10. The simulation defect sample 10 is so attached to the defect inspecting device that the simulation defect 13 is diagonal to the scan line of the defect inspecting device. Since a simulation defect equivalent to a standard defect output is constituted by the laser marking device 12, similar output is provided at any position. Adjustment of sensitivity of the defect inspecting device, or the like is easily performed with high precision.

